Examiner

"EXAMPLER: Instal I referen

Sheet 1	1 of 1										
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<i>FL1</i>	AA	6,589,879	7/8/2003	Williams, et al.		438		714		_	
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th1	AC	4,857,477	8/15/1989	Kanamori		437		47			
7h1	AD	6,235,643	5/22/2001	Mui, et al.		438		719			
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2h1	AJ	S. Wolf, "Silicon Processing for the VLSI Era", Vol. II, Process Integration, 1990, pages 51-54									
The	AK	Ti's "Trench Technology Moves in the Factory", Electronics, July 9, 1987, pages 75-87									
the	AL	R. N. Carlile, et al. "Trench Etches in Silicon with Controllable Sidewall Angles", Electrochem. Soc. Solid-State Science and Technology, August 1988, pages 2058-2064									
th1	AM	G. K. Herb, et al., "Silicon Trench Etch in a Hex Reactor", Solid State Technology, October 1987, pages 109-115									

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